

## AlGaAs/GaAs Low Noise Microwave HEMT CHIP

**Description**

The 2SK676H5 is an AlGaAs/GaAs HEMT chip fabricated by MOCVD (Metal Organic Chemical Vapor Deposition). This 0.5 micron gate FET features very low noise figure and high gain, and is suitable for a wide range of front-end amplifier applications including satellite reception and other communications systems up to K-band.

**Features**

- Low noise figure
- Excellent device uniformity
- High gain
- Wide band

**Structure**

AlGaAs/GaAs N-channel HEMT chip

Twin gate-pad  $\pi$  geometry

**Absolute Maximum Ratings (Ta=25°C)**

• Drain to source voltage	V <sub>Ds</sub>	5	V
• Gate to source voltage	V <sub>GSO</sub>	-3.5	V
• Drain current	I <sub>D</sub>	70	mA

**Electrical Characteristics**

Ta=25°C

Item	Symbol	Condition		Min.	Typ.	Max.	Unit
Gate to source cutoff current	I <sub>GSS</sub>	V <sub>Ds</sub> =0V, V <sub>Gs</sub> =-3V				-100	$\mu$ A
Drain current	I <sub>DS</sub>	V <sub>Ds</sub> =2V, V <sub>Gs</sub> =0V		10	40	70	mA
Gate to source cutoff voltage	V <sub>GSO(OFF)</sub>	V <sub>Ds</sub> =2V, I <sub>D</sub> =500 $\mu$ A		-0.2	-1.5	-3.0	V
Forward transfer admittance	Y <sub>fs</sub>	V <sub>Ds</sub> =2V, I <sub>D</sub> =10mA		25	40		ms
Noise figure	NF	V <sub>Ds</sub> =2V, I <sub>D</sub> =10mA	f=12GHz			1.4	dB
Associated gain at NF min.	G <sub>a</sub>	V <sub>Ds</sub> =2V I <sub>D</sub> =10mA	f=12GHz	9	11		dB

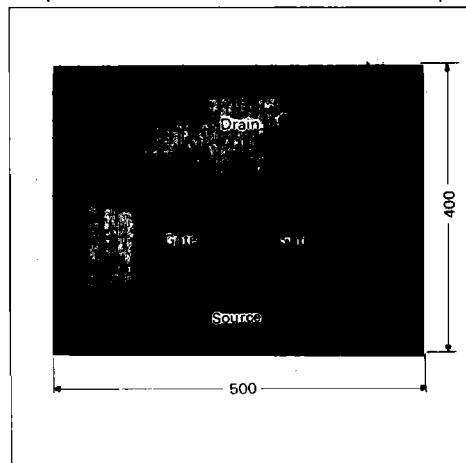
Noise figure ranks determined on a sampling basis by measuring ceramic-mounted devices.

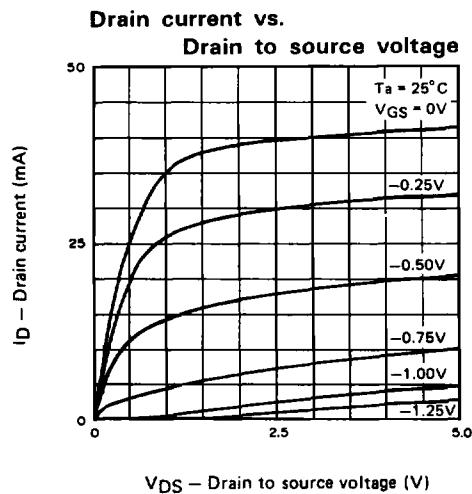
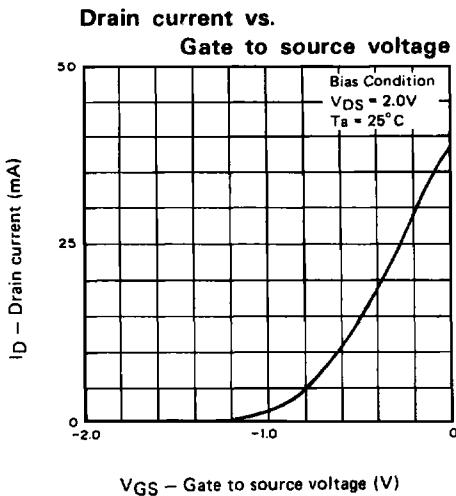
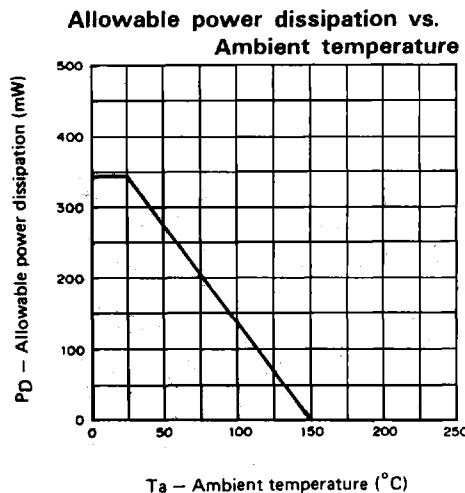
**Noise Figure Classification (f=12 GHz)**

	Min.	Typ.	Max.	
2SK676H5-1	—	—	1.0	
2SK676H5-2	—	—	1.2	dB
2SK676H5-3	—	—	1.4	

**Chip outline**

Unit:  $\mu$ m



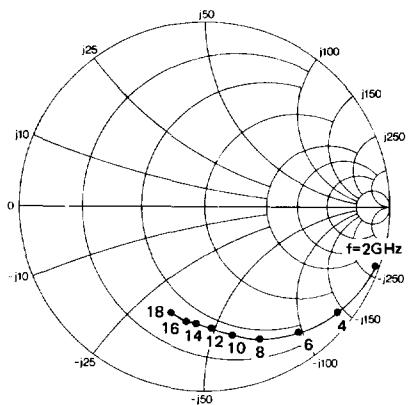


## S-Parameters vs. Frequency Characteristics

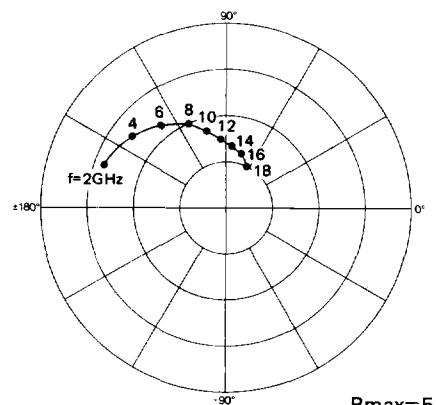
 $V_{DS}=2V, I_D=10\text{ mA}$ 

f (GHz)	S11		S21		S12		S22	
	MAG	ANG	MAG	ANG	MAG	ANG	MAG	ANG
2	0.976	-20.0	3.415	161.1	0.030	79.2	0.744	-10.1
4	0.916	-38.6	3.164	143.8	0.057	69.8	0.723	-19.0
6	0.852	-54.2	2.819	129.4	0.076	62.2	0.700	-27.2
8	0.775	-67.7	2.482	115.3	0.089	55.9	0.671	-32.6
10	0.717	-78.3	2.154	105.0	0.096	52.8	0.657	-37.2
12	0.667	-87.2	1.897	94.4	0.103	52.6	0.644	-41.4
14	0.631	-93.7	1.666	85.4	0.103	55.0	0.648	-45.1
16	0.625	-99.4	1.542	75.4	0.105	58.8	0.627	-47.8
18	0.605	-106.8	1.237	63.6	0.123	62.6	0.645	-46.7

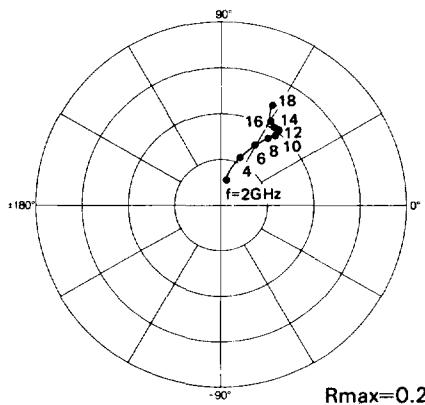
S11



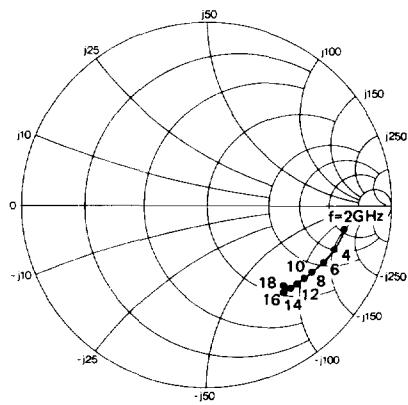
S21

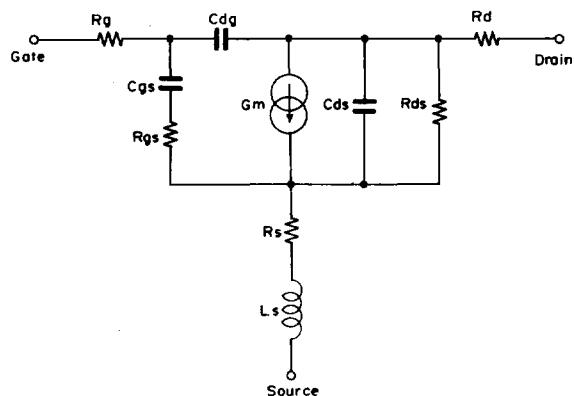
 $R_{max}=5$ 

S12

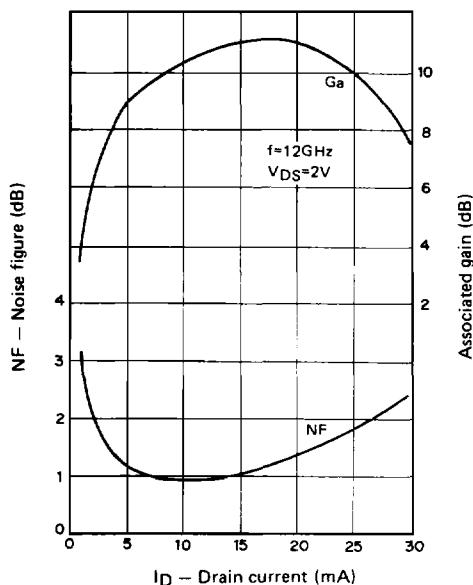
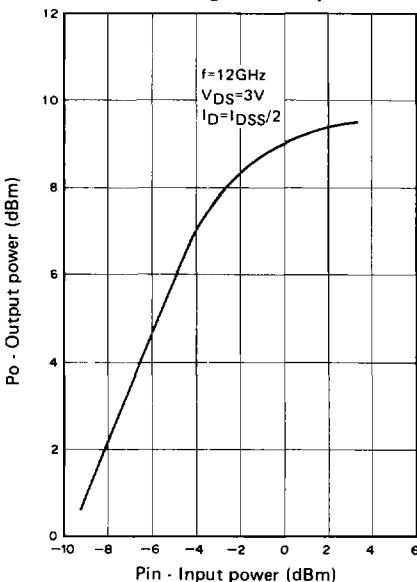


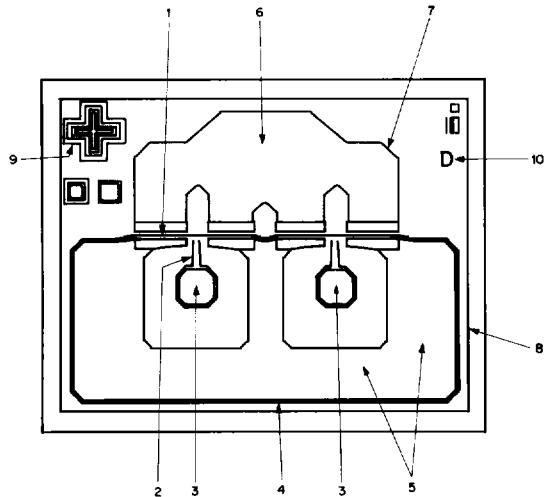
S22

 $R_{max}=0.2$

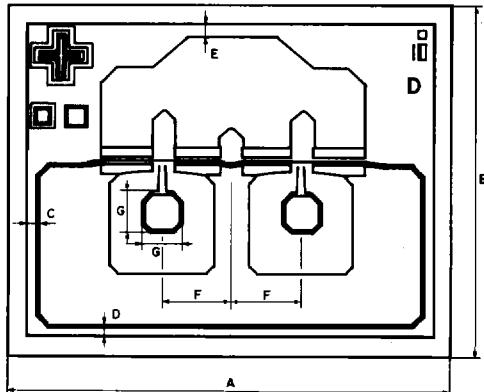
**Equivalent Circuit** $V_{DS}=2V, I_D=10\text{ mA}$ 

Parameter	Value
R <sub>g</sub>	1Ω
C <sub>gs</sub>	0.23 pF
R <sub>gs</sub>	3.5Ω
G <sub>m</sub>	50 mS
C <sub>ds</sub>	0.06 pF
R <sub>ds</sub>	300Ω
R <sub>d</sub>	1Ω
R <sub>s</sub>	3.5Ω
L <sub>s</sub>	0.08 nH
C <sub>dg</sub>	28 fF

**Minimum noise figure vs.  
Drain current****Output power at 1 dB  
gain compression**

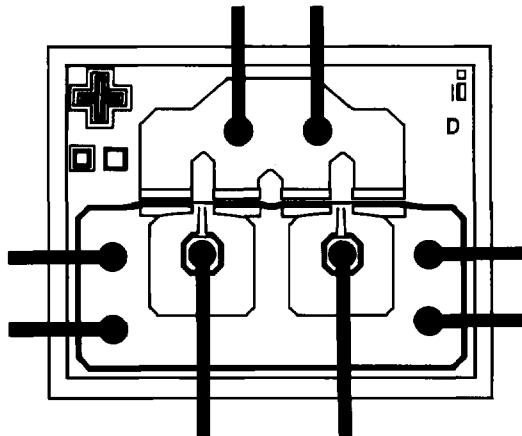
**Chip Outline**

1. Gate area
2. Gate metal
3. Gate bonding pad
4. Source metal
5. Source bonding pad
6. Drain bonding pad
7. Drain metal
8. Scribe line
9. Alignment mark
10. D: 2SK676H5

**Chip Pattern Dimension**

Symbol	Dimension ( $\mu\text{m}$ )
A	500 $\pm$ 50
B	400 $\pm$ 50
C	15 $\pm$ 3
D	10 $\pm$ 3
E	15 $\pm$ 3
F	75 $\pm$ 5
G	44 $\pm$ 5

Chip thickness  $150 \pm 30 \mu\text{m}$   
Pad metal Au  $1 \pm 0.15 \mu\text{m}$   
Back metal Ti/Au  $0.45 \pm 0.05 \mu\text{m}$

**Recommended Bonding Position****HEMT Chip Handling Precautions**

- 1) All handling and assembly operations should be done in a clean and dry environment.
- 2) Chips should be stored in a dry nitrogen environment at room temperature.
- 3) Care must be exercised when handling GaAs chips, since they break easily under pressure.
- 4) All equipment used for handling, die attachment, and wire bonding must be properly grounded to avoid electrostatic damage to the chips.
- 5) Die attachment: Use AuSn alloy in nitrogen atmosphere. The temperature should be 280 to 300°C, and the operation time should be kept as short as possible. When using Ag paste, cure for one hour at 160°C in a nitrogen atmosphere.
- 6) Wire bonding: Thermal compression wedge bonding is recommended. The temperature should be under 290°C, and the operation time should be kept under a minute. Bonding wire diameter should be 0.7 to 1.0 mils (18 to 25 microns) diameter gold. Wire lengths should, in general, be kept as short as possible.

## Packaging

The chip is placed on the film carrier and numbered as shown in the figure, starting in the top left corner.

A	1								10
B	11								20
C	21								30
D	31								40
E	41								50
F	51								60
G	61								70
H	71								80
I	81								90
J	91								100
	1	2	3	4	5	6	7	8	9 10